EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	27	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and etch$3.clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:52
L2	0	"6475369".pn. And clean$3 with anode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:53
L3	1	"6475369".pn. And etch$3 with anode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:58
L4	1	"6475369".pn. And pulse	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:59
L5	1	"6475369".pn. And puls$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 14:08
L6	7	"734223".ap.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 14:09
S1	54	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 13:34
S2	13	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and clean$3 with (mask electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/28 13:39

S3	0	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and clean$3 with (electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 13:55
S4	2209	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and clean$3 with (electrode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:24
S5	99	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and (clean$3 with (electrode)) with (etching anodizing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:34
S6	19	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and (clean$3 with (electrode)) with (anodizing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:41
S7	19	("205"/$.ccls. "204"/$.ccls.) and (clean$3 with (electrode)) with (anodizing)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:41
S8	0	("205"/$.ccls. "204"/$.ccls.) and (clean$3 with (electrode)) with (anodizing) not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:42
S9	445	("205"/$.ccls. "204"/$.ccls.) and (electrode) with (anodizing) not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:42
S10	31	("205"/$.ccls. "204"/$.ccls.) and (electrode) with (anodizing) and clean$3 with (electrode) not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 14:42

S11	9	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and pulse$2 with (current voltage)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:07
S12	9	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and frequency	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:09
S13	6585	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and frequency	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:09
S14	58	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and frequency and periodic with reverse	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:17
S15	1720	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and frequency with (hz khz)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:18
S16	370	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and frequency with (hz khz) and pulse with current	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:21
S17	161	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) same frequency with (hz khz) and pulse with current	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:36
S18	0	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and sequestering	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:43

S19	20	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and sequestering same edta	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:46
S21	0	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and conformable with mask and edta	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:43
S22	276	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and complexing same edta	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:46
S23	41	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and complexing same edta same advantag$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 15:51
S24	16	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and complexing same edta same solubility	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:02
S25	89	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and wetting and accelerator and suppressor and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:04
S26	206	("205"/$.ccls. "204"/$.ccls.) and (electrolysis electrolytic electrochemic$4 plating electrodeposit$5 electroplat$5) and (carrier wetting) and (brightener accelerator) and suppressor and leveler	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/27 16:05